Studies were conducted on Si-doped TiN coatings on stainless steel. The coatings were deposited by reactive magnetron sputtering at different target currents. Prior to deposition of the TiN coating, a buffer layer of Ti (approx 100nm) was deposited to aid adhesion of the TiN coating to the steel substrate. The XRD patterns for coatings deposited at different target currents are shown below.

Based on the XRD patterns, identify three changes in the structure of the coatings that occur as the current increases. What is the XRD evidence for those changes?